

## REMARKS

Favorable reconsideration of this application and the Office Action of December 28, 2008 are respectfully requested in view of the foregoing amendments and the following remarks.

Claims 1 to 14 remain in this application as amended. Basis for the amendment to claims 1 and 5 is found in the specification at page 3, lines 20-25.

The objection to claim 5 has been obviated by correcting the misspelling of photoresist.

The rejection of claim 10 under 35 U.S.C. 112, second paragraph, has been obviated by replacing "exposed" to "treated" as kindly suggested by the Examiner.

The rejection of claims 1-6 and 10-14 under 35 U.S.C. 102(a) as anticipated by Hendricks et al. (WO 02/09103), the rejection of claim 7 under 35 U.S.C. 103(a) as unpatentable over Hendricks et al. in view of Peterson et al. (US 5,702,767), and the rejection of claims 8-9 under 35 U.S.C. 103(a) over Hendricks et al. in view of Peterson et al. further in view of Thompson (US 6,361,921) are all respectfully traversed. All three of these rejections are based on Hendricks et al. as the primary reference and the deficiency of this primary reference disclosure, which is not cured by any of the secondary references, renders all three rejections erroneous.

The disclosure in Hendricks et al. does not disclose that there is a gradient to the normal in the sensitivity in the photoresist in the stack. According to Hendricks et al. the undercoat is fully cross-linked and only the top photoresist layer is sensitive to light for the recording process.

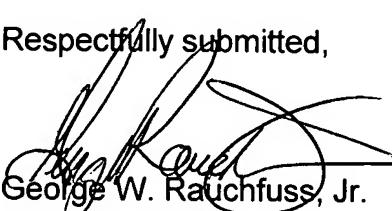
Furthermore, Hendricks et al. relates to a method for fabricating a stamper plate. However, the claims of the present invention relate to a **master plate** for fabricating a

stamper plate. Specifically, the method disclosed in Hendricks et al. on page 3, lines 22-25 relates to a direct stamper recording (DSR) process, a process that is without the use of a master plate. Thus, the disclosure in Hendricks et al. does not anticipate claims 1-6 and 10-14. Neither Hendricks et al., Peterson et al., nor Thompson teach a gradient in the solubility along the normal to the photoresist layer. Since these deficiencies in Hendricks et al. are not cured by the disclosures in either Peterson et al. or Thompson, the rejection of claims 7-9 are likewise deficient and erroneous. Therefore, the USPTO is respectfully requested to reconsider and withdraw all three of these prior art rejections.

It is respectfully submitted that this is a full and complete response to the Office Action of December 28, 2007 and that all the claims are allowable for at least the reasons stated. An early indication of their allowability by issuance of a Notice of Allowance is earnestly solicited.

Respectfully submitted,

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